

| L Number | Hits | Search Text | DB | Time stamp |
|----------|--------|----------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------|---------------------------------|---------------------|
| 1 | 325 | ((stress or stresses or stressed) and ((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective))) and (nmrms or rms) | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:48 |
| 2 | 176 | ((stress or stresses or stressed) and ((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective))) and (euv or (enhanced adj ultraviolet) or duv) | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:20 |
| 3 | 6085 | 430/5.ccls. | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:20 |
| 4 | 1132 | 378/34-35.ccls. | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:21 |
| 5 | 33 | 430/5.ccls. and (((stress or stresses or stressed) and ((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective))) and (euv or (enhanced adj ultraviolet) or duv)) | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:22 |
| 6 | 18 | 378/34-35.ccls. and (((stress or stresses or stressed) and ((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective))) and (euv or (enhanced adj ultraviolet) or duv)) | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:47 |
| 7 | 63130 | warp or warping | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:47 |
| 8 | 292657 | mask or photomask or reticle | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:47 |
| 9 | 473652 | reflect or reflection or reflectance or reflective | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:48 |
| 10 | 33754 | nmrms or rms | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:48 |
| 11 | 894697 | flatness or flat | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:48 |
| 12 | 3293 | euv or (enhanced adj ultraviolet) or duv | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:48 |
| 13 | 51827 | ((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective) | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:48 |
| 14 | 1258 | (warp or warping) and ((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective)) | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:48 |
| 15 | 133 | (nmrms or rms) and ((warp or warping) and ((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective))) | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:48 |
| 16 | 442035 | stress or stresses or stressed | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:49 |
| 17 | 6897 | ((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective)) and (stress or stresses or stressed) | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:49 |
| 18 | 34 | ((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective)) and (stress or stresses or stressed)) and ((nmrms or rms) and ((warp or warping) and ((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective)))) | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:51 |

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| 19 | 444 | ((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective)) and (stress or stresses or stressed)) and ((warp or warping) and ((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective))) | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:51 |
| 20 | 6931 | 430/5.ccls. or 378/34-35.ccls. | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:51 |
| 21 | 21 | ((((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective)) and (stress or stresses or stressed)) and ((warp or warping) and ((mask or photomask or reticle) and (reflect or reflection or reflectance or reflective)))) and (430/5.ccls. or 378/34-35.ccls.) | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:53 |
| 22 | 2716 | buffer with (stress or stresses or stressed) | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:53 |
| 23 | 10 | (430/5.ccls. or 378/34-35.ccls.) and (buffer with (stress or stresses or stressed)) | USPAT; US-PGPUB; EPO; JPO | 2003/06/27 14:56 |